

<sup>5</sup><sub>54</sub>. (amended) A method for forming a relief image on a substrate comprising:  
applying on the substrate a layer of an antihalation composition comprising an  
anthracene material;

B2 applying over the antihalation composition coating layer a photoresist composition.

<sup>6</sup><sub>55</sub>. (amended) The method of claim <sup>5</sup><sub>54</sub> wherein the antihalation composition  
coating layer is crosslinked prior to applying the photoresist composition.

✓  
[ Please add the following new claims.

<sup>13</sup><sub>58</sub>. The method of claim <sup>5</sup><sub>54</sub> wherein the photoresist composition is imaged with  
activating radiation and the imaged photoresist composition is treated with a developer to  
provide a photoresist relief image.

<sup>14</sup><sub>59</sub>. The method of claim <sup>13</sup><sub>58</sub> wherein areas bared of photoresist upon treatment with  
the developer are etched.

<sup>15</sup><sub>60</sub>. The method of claim <sup>13</sup><sub>58</sub> wherein areas bared of photoresist upon treatment with  
the developer are exposed to a plasma gas.

B3 <sup>5</sup><sub>61</sub>. The method of claim 58 wherein the plasma gas penetrates the antihalation  
composition coating layer.

<sup>7</sup><sub>62</sub>. The method of claim <sup>6</sup><sub>55</sub> wherein the photoresist composition is imaged with  
activating radiation and the imaged photoresist composition is treated with a developer to  
provide a photoresist relief image.